

**Amendments to the Claims:**

Please cancel Claims 21 and 59 – 62 without prejudice or disclaimer, and amend Claim 18 as indicated by the following listing of claims, which replaces all prior versions and listings of claims in the application.

**Listing of Claims:**

1. – 17. (Canceled)

18. (Currently Amended) A plasma processing system comprising:

a first substrate support structure configured to hold a first substrate in an undivided processing chamber compartment;

a second substrate support structure configured to hold a second substrate in the undivided processing chamber compartment; and

a transformer-coupled plasma generator within the undivided processing chamber compartment disposed between the first substrate support structure and the second substrate support structure.

19. (Original) The plasma processing system of claim 18 wherein the transformer-coupled plasma generator includes a toroidal transformer core.

20. (Original) The plasma processing system of claim 18 wherein the plasma generator comprises a plasma generating plate having a plurality of transformer cores within the plasma generating plate and a plurality of through holes forming conduits from a first side of the plate to a second side of the plate.

21. – 52. (Canceled).

53. (Previously Presented) The plasma processing system of claim 19 wherein the first and second substrate support structures are substantially parallel.

54. (Previously Presented) The plasma processing system of claim 53 wherein a plane of the toroidal transformer core is substantially parallel to the first and second substrate support structures.

55. (Previously Presented) The plasma processing system of claim 20 wherein the transformer-coupled plasma generator further includes a second conduit not passing through a transformer core.

56. (Previously Presented) The plasma processing system of claim 20 wherein the plasma generating plate is flat.

57. (Currently Amended) The plasma processing system of claim ~~[[20]]~~ 19 wherein the toroidal transformer core comprises ferrite material.

58. (Previously Presented) The plasma processing system of claim 20 wherein the plasma generating plate includes a dielectric spacer between the first side and the second side, and a remainder of an outer surface of the plasma generating plate comprises an electrical conductor.

59. – 62. (Canceled).